Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L4	7121	134/2,32,33,94.1,99.2,137,144, 151,153,902.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/05 13:29
L5	366	4 and (semiconductor or wafer or substrate) and roller	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/05 14:02
L6	10	5 and (roller with (suction or vacuum))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/05 14:09
L7	457	15/77,103.5,102.ccls. and roller	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/05 14:09
L8	205	7 and (semiconductor or wafer or substrate) and roller	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/05 14:02
L9	48	8 and (suction or vacuum)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/05 15:21
L10	848	15/302,303,306.1.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/05 14:09
L11	172	10 and roller	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/05 14:09
L12	118	11 and (suction or vacuum)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/05 15:06

L13	111	5 and ((suction or vacuum))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/05 14:09
L14	262	9 or 12 or 13	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/05 14:10
L15	124	(john near2 ((de adj larios) or delarios)).in. or (carl near2 woods).in. or (james near2 garcia).in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/10/05 14:14
L16	34	L15 and roller	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/10/05 14:20
L19	100	14 and (roller same (suction or vacuum))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/05 15:21
L20	2024	34/407,58,92.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/05 15:21
L21	106	20 and roller and (suction or vacuum)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/05 15:21
S4	124	(john near2 ((de adj larios) or delarios)).in. or (carl near2 woods).in. or (james near2 garcia).in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/09/29 08:58
S5	31	S4 and proximity	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/10/05 14:14
S11	2	S5 and edge adj roller	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/09/29 11:09

S12	2	S11 and proximity adj head	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/09/29 11:21
S13	19199	(semiconductor or wafer or substrate) and (edge near3 (remov$3 or clean$3 or etch$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/09/29 11:35
S14	2711	S13 and roller	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/09/29 11:35
S15	762	S13 and (edge with roller)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/09/29 11:35
S16	1611743	S15 adn (vacuum or suction)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/09/29 11:36
S18	295	S15 and (vacuum or suction)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/09/29 13:04